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ABSTRACT

This invention is an apparatus for imaging metrology, which in particular embodiments
may be integrated with a processor station such that a metrology station is apart from but
coupled to a process station. The metrology station is provided with a first imaging camera
with a first field of view containing the measurement region. Alternate embodiments include a
second imaging camera with a second field of view. Preferred embodiments comprise a
broadband ultraviolet light source, although other embodiments may have a visible or near
infrared light source of broad or narrow optical bandwidth. Embodiments including a broad
bandwidth source typically include a spectrograph, or an imaging spectrograph. Particular
embodiments may include curved, reflective optics or a measurement region wetted by a
liquid. In a typical embodiment, the metrology station and the measurement region are
configured to have 4 degrees of freedom of movement relative to each other.